

Fig.1 SEM morphology of Mo film

Molybdenum (Mo) is a high temperature melting point metal which is used in a wide range of applications from electrodes in photovoltaic to hard coatings. The deposition rate of PPD at 100 Hz is 10 times larger compared to sputtering. Moreover it may be deposited by at room temperature on different substrates.

The SEM cross section image shows in the inset shows that the film is compact and smooth making it a suitable electrode for PV applications. The temperature deposition allows to make hetero-multilayer without limitations in the deposition sequence.

AFM image in Fig. 2 indicates the smoothness.

Typical properties of Mo thin films are the following:

Temperature °C	Roughness nm r.m.s.	Deposition rate Gun IV @90Hz nm/min	Deposition rate Gun V @100Hz nm/min	Substrate
RT	7,3	15	50	SiO ₂

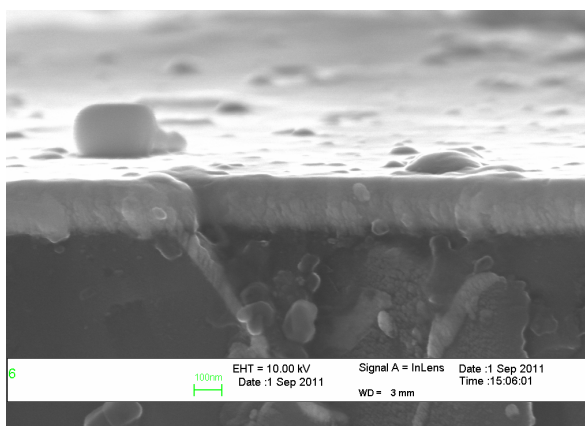


Fig. 2 SEM cross section of Mo film